

## MINILAB 125

Flexible, modular systems for high-quality physical vapour deposition



### Key Features:

- Front-loading box-type vacuum chamber
- Modular design
- Turbomolecular pumping systems
- Base pressures  $< 5 \times 10^{-7}$  mbar
- Thermal evaporation
- Low-temperature evaporation (LTE)
- Electron-beam evaporation
- Magnetron sputtering
- Metals, dielectrics and organics deposition
- Up to 11" diameter substrates
- Variety of load-lock options
- Touchscreen HMI for system control
- Equipped for easy servicing
- Comprehensive safety features
- Proven performance

### MiniLab Systems — Overview:

MiniLab systems from Moorfield provide superior coating performance, with the flexibility and modularity of design to address a huge range of customer requirements. The MiniLab range consists of several platforms. Each platform is generally associated with a specific vacuum chamber size. While all chambers are built to the same standards, and allow for high-vacuum operation, larger chambers allow for more techniques and flexibility than their smaller counterparts. In addition to thin-film deposition, MiniLab systems can also be fitted with complementary techniques such as ion beam sources, etching components, and annealing stages.

### MiniLab 125 Platform:

MiniLab 125 systems are floor-standing vacuum evaporators for metal, dielectric and/or organics thin-film deposition. All systems contain a box-type stainless-steel chamber with front door for loading/unloading. A turbomolecular pumping system is standard, for high-vacuum base pressures of better than  $5 \times 10^{-7}$  mbar. Exact configuration is extremely flexible and dependant on customer budgets and applications.

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## Configuration and Options:

The MiniLab 125 base configuration includes a turbomolecular pump positioned on a port at the rear of the vacuum chamber. The chamber sits on a double-rack frame that contains system control electronics and power supplies. MiniLab 125 systems are available with load-locks — please call for details.

The system can be equipped with a wide variety of deposition techniques. These include thermal and low-temperature evaporation sources (for metals and organics), magnetron sputtering cathodes (for metals and inorganics), and electron-beam sources (for most material classes except organics).



Above: Examples of deposition sources available for the MiniLab 125. From left to right: Moorfield TE1 source for standard thermal evaporation, Moorfield LTE-1CC source for low-temperature evaporation (LTE), Moorfield *Flexi-Head* MAGNETRON source for magnetron sputtering, and Telemark multi-pocket water-cooled electron-beam source.

Deposition sources are typically mounted on the chamber base-plate, but sputter-down configurations are also available. Substrate stages, usually at the top of the chamber, can accommodate substrate sizes up to 11" diameter. Substrate heating, rotation, bias and z-shift are available, together with source and substrate shutters. Examples of configurations for specific applications are listed below.

**Thermal evaporation:** Up to 4 thermal evaporation sources. Moorfield TE1, TE2, TE3 or TE4 configurations available. Water-cooled power feedthroughs and boxed shielding for excellent vacuum maintenance and low contamination. Power supplies available for automatic, manual, sequential- and co-deposition.

**Low-temperature evaporation (LTE):** Up to 4 organics sources. Moorfield LTE-1CC, LTE-2CC and LTE-5CC models available. Alumina or quartz crucibles. Power supplies equipped for temperature and power control, in automatic and manual modes.

**Magnetron sputtering:** Up to six Moorfield MAGNETRON sources for 2", 3" or 4" industry-standard targets (easy fitting/removal). RF, DC or pulsed DC power supplies, fully integrated with system touchscreen controller. Various gas and pressure control packages, including MFCs for process gas introduction. Throttle valve for protecting pumping system from gas loads.

**Electron-beam evaporation:** Telemark multi-pocket (e.g., 6 × 7 CC or 8 × 4 CC) electron-beam evaporation sources. Sources are water-cooled and can be connected to automated pocket indexer modules. Ferrotec 3 kW, 5 kW and 10 kW power supplies available.

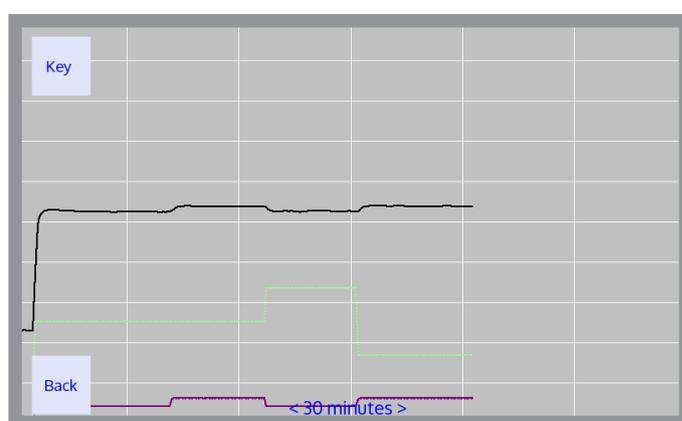
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**Multi-technique systems:** Various combinations of all of the above can be included in MiniLab 125 systems.

For all techniques, deposition rate monitoring (via quartz crystal sensor heads) together with thin-film monitors and controllers are available.

## Control System:

The unit is fitted with high-stability, industrial-grade PLC electronics. User operation is via a 7" touchscreen HMI mounted on the front panel. Powerful but easy-to-use software allows for system setup and operation via a menu-driven interface (note that manual control via electronics rack front panels is also possible, depending on exact system configuration). *IntelliNet* software allows for data-logging and diagnostics to a connected PC.



Above: Screenshots from the touchscreen HMI software through which MiniLab 125 general control is carried out.

## Technical Specification:

**Chamber:** 500 mm (width) × 500 mm (depth) × 650 mm (height) stainless-steel front-loading box chamber with D-shaped back. Hinged front door for easy access. Chamber base-plate, top and sides fitted with ports for in-chamber hardware. Shuttered viewport(s) for process observation. Viton o-ring seals.

**Safety interlocks:** Water and vacuum levels.

**Pumping group:** Water-cooled Edwards or Leybold turbomolecular pumps, up to 1500 L/s. Edwards rotary or dry scroll-type backing pumps up to 35 m<sup>3</sup>/hour.

**Pressure measurement:** Wide-range gauge (Edwards or Inficon) and optional capacitance manometers for high-resolution measurement.

**Substrate stages:** Stainless steel, aluminium or copper with threaded holes for substrate attachment. or up to 11" diameter substrates. Optional rotation, heating, cooling, bias and z-shift modules.

**Deposition sources:** Various types depending on requirements (see above). Separate brochures available for all Moorfield source types.

**Power supplies:** Various types depending on integrated techniques. All power supplies fully integrated within system electronics rack.

**System control:** Industrial-grade, high-stability PLC electronics core. Designed for safe operation and reliable vacuum integrity.

**Deposition monitoring and control:** Various components including the Inficon SQM-160 (2-channel

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monitor) and Inficon SQC-310 (process controller).

**Weight:** Approximately 100–200 kg; dependant on configuration.

**Size:** 1700 mm (height) × 590 mm (depth) × 1180 mm (width); dependant on configuration.



Left: MiniLab 125 chamber interior, with 3 magnetron sputtering sources for 4" diameter targets arranged in a sputter-down configuration. At the bottom of the chamber is a 1000 °C substrate heating stage with bias, quartz crystal sensor heads for deposition rate/thickness control and various shutters. Right: MiniLab 125 system with extended control rack. System is configured for magnetron sputtering and is equipped with automatic process control.

## System Requirements—Basic Configuration:

- Process gases: 25 psi supplies, 99.99% purity or better
- Service gas: Dry compressed air nitrogen or argon, 60–80 psi supply
- Vent gas: N<sub>2</sub>, 0.5 bar
- Power: Single-phase 230 V, 50 Hz, 13 A
- Chilled water: 18–20 °C, 3 L/min, pressure < 4 bar
- Exhaust extraction

## Applications:

- Fundamental research
- Education
- Product R&D

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